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| U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified) | | | | | Docket No. 8235/ETCH/DRIE/JB1 | | Serial No. 10/674,700 | |
| INFORMATION DISCLOSURE STATEMENT BY APPLICANT | | | | | Applicant Ye, et al. | | Confirmation No.: | |
| (Use several sheets if necessary) | | | | | Filing Date 09/29/2003 | | Group | |
| Examiner | | | | | | | | |
| U.S. Patent Documents | | | | | | | | |
| *Examiner Initial | | Document Number | Issue Date | Applicant(s) Name | Class | Subclass | Filing Date If Appropriate | |
| L.T.M.-E | A1 | 6,514,672 | 02/04/2003 | Young et al. | 430 | 314 | | |
| L.T.M.-E | A2 | 2001/0046632 | 11/29/2001 | Young et al. | 430 | 5 | 06/11/2001 | |
| | A3 | | | | | | | |
| | A4 | | | | | | | |
| | A5 | | | | | | | |
| | A6 | | | | | | | |
| | A7 | | | | | | | |
| | A8 | | | | | | | |
| | A9 | | | | | | | |
| | A10 | | | | | | | |
| | A11 | | | | | | | |
| | A12 | | | | | | | |
| Foreign Patent Documents | | | | | | | | |
| *Examiner Initial | | Document Number | Date | Country | Class | Subclass | Translation | |
| | | | | | | | YES | NO |
| | B1 | | | | | | <input type="checkbox"/> | <input type="checkbox"/> |
| | B2 | | | | | | <input type="checkbox"/> | <input type="checkbox"/> |
| | B3 | | | | | | <input type="checkbox"/> | <input type="checkbox"/> |
| | B4 | | | | | | <input type="checkbox"/> | <input type="checkbox"/> |
| OTHER ART | | | | | | | | |
| *Examiner Initial | | Including Author, Title, Date, Pertinent Pages, Etc. | | | | | | |
| L.T.M.-E | C1 | Mahorowala, et al., "Transfer Etching of Bilayer Resists in Oxygen-based Plasmas," Journal of Vacuum Science & Technology A: Vacuum, Surfaces, and Films 18 (4), 1411-1419 (July 2000). | | | | | | |
| | C2 | | | | | | | |
| | C3 | | | | | | | |
| Examiner <i>Lynette T. Umeg-Ewuruni</i> | | | | | Date Considered <i>9/29/2005</i> | | | |
| *EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant. | | | | | | | | |